

WHAT IS CLAIMED IS:

1. A substrate cleaning device, comprising:

a first cleaning room including a first cleaning portion for cleaning a substrate placed therein; and

a second cleaning room including a second cleaning portion for cleaning a substrate provided therein,

wherein the first cleaning room is stacked on the second cleaning room so that at least a portion of the first cleaning room overlaps at least a portion of the second cleaning room.

2. A substrate cleaning device according to claim 1, further comprising a filter provided in an overlapping region of the first cleaning room and the second cleaning room.

3. A substrate cleaning device according to claim 1, wherein:

a first table is provided in the first cleaning room, and the first table is slid with the substrate placed in the first cleaning room being placed on the first table; and

a second table is provided in the second cleaning

room, and the second table is slid with the substrate placed in the second cleaning room being placed on the second table.

4. A substrate cleaning device according to claim 1, wherein the first cleaning room is open so that clean air flows into the first cleaning room.

5. A substrate cleaning device according to claim 1, wherein:

a first opening portion is provided on a side wall of the first cleaning room; and

a second opening portion is provided on a side wall of the second cleaning room.

6. A substrate cleaning device according to claim 5, wherein the side wall of the first cleaning room provided with the first opening portion is opposite to the side wall of the second cleaning room provided with the second opening portion.

7. A substrate cleaning device according to claim 1, wherein:

the first cleaning portion comprises a first nozzle

head having a first blowing portion for blowing gas onto the substrate placed in the first cleaning room and a first suctioning portion for suctioning the gas in the first cleaning room; and

the second cleaning portion comprises a second nozzle head having a second blowing portion for blowing gas onto the substrate placed in the second cleaning room and a second suctioning portion for suctioning the gas in the second cleaning room.

8. A substrate cleaning device according to claim 1, wherein the first cleaning room and the second cleaning room are arranged so that when the first cleaning room and the second cleaning room are projected onto a plane perpendicular to a vertical direction, the area of an overlapping region of images thereof on the plane is maximized.

9. A substrate processing facility, comprising a clean room, wherein:

a substrate cleaning device is provided in the clean room; and

the substrate cleaning device comprises:

a first cleaning room including a first

cleaning portion for cleaning a substrate placed therein;  
and

a second cleaning room including a second cleaning portion for cleaning a substrate provided therein,

wherein the first cleaning room is stacked on the second cleaning room so that at least a portion of the first cleaning room overlaps at least a portion of the second cleaning room.

10. A substrate processing facility according to claim 9, wherein:

a first table is provided in the first cleaning room, and the first table is slid with the substrate placed in the first cleaning room being placed on the first table;  
and

a second table is provided in the second cleaning room, and the second table is slid with the substrate placed in the second cleaning room being placed on the second table.

11. A substrate processing facility according to claim 10, wherein a first loading apparatus for placing the substrate on the first table in the first cleaning room and a second

loading apparatus for placing the substrate on the second table in the second cleaning room are provided in the clean room.

12. A substrate processing facility according to claim 10, wherein the first loading apparatus and the second loading apparatus are arranged substantially on a line with the substrate cleaning device being sandwiched between the first loading apparatus and the second loading apparatus in the clean room.